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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/525,240	05/13/2005	Koji Miyata	Q86264	7140
23373 7590 05/27/2010 SUGHRUE MION, PLLC		EXAMINER		
2100 PENNSYLVANIA AVENUE, N.W.			CROWELL, ANNA M	
SUITE 800 WASHINGTON, DC 20037			ART UNIT	PAPER NUMBER
			1716	
			NOTIFICATION DATE	DELIVERY MODE
			05/27/2010	ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

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sughrue@sughrue.com PPROCESSING@SUGHRUE.COM USPTO@SUGHRUE.COM

	Application No.	Applicant(s)
	10/525,240	MIYATA ET AL.
Office Action Summary	Examiner	Art Unit
	Michelle Crowell	1716
The MAILING DATE of this communication ap	pears on the cover sheet with the c	correspondence address
Period for Reply		
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period. - Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailine earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION 136(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	N. mely filed the mailing date of this communication. ED (35 U.S.C. § 133).
Status		
Responsive to communication(s) filed on <u>09 A</u> This action is FINAL . 2b) ☑ This Since this application is in condition for allowed closed in accordance with the practice under the practice under the practice.	s action is non-final. ance except for formal matters, pro	
Disposition of Claims		
4) Claim(s) 2-21 is/are pending in the application 4a) Of the above claim(s) 2-5 and 7-19 is/are v 5) Claim(s) is/are allowed. 6) Claim(s) 6 and 20-21 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/o	withdrawn from consideration.	
Application Papers		
9) The specification is objected to by the Examina 10) The drawing(s) filed on is/are: a) accomposed as a composition and applicant may not request that any objection to the Replacement drawing sheet(s) including the correct and the correct of the control of the correct of the control of the correct of the correct of the control of the correct of the control of the correct of the control of the correct of the correc	cepted or b) objected to by the drawing(s) be held in abeyance. Section is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documen 2. Certified copies of the priority documen 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	nts have been received. Its have been received in Applicat Pority documents have been receive Tau (PCT Rule 17.2(a)).	ion No ed in this National Stage
Attachment(s)		
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date 	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:	ate

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DETAILED ACTION

Election/Restrictions

- 1. Applicant's election without traverse of Species III, Figure 12 (claims 6, 20, 21) is acknowledged.
- 2. Claims 2-5 and 7-19 are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected species, there being no allowable generic or linking claim.

Continued Examination Under 37 CFR 1.114

3. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on April 9, 2010 has been entered.

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any

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evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

6. Claims 6 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ito et al. (JP 2001-338912) or Morimoto (J.P. 2001-077095) in view of Nishijima et al. (06-181187).

Referring to Drawings 1 and 2 and paragraphs [0025]-[0033], Ito et al. discloses a magnetic field generator 21 for magnetron plasma, comprising a plurality of magnetic segments 22 provided on the outer side of a process chamber 1 for performing a predetermined process on a substrate placed in said chamber for generating a multi-pole magnetic field 25 along the circumference of said substrate.

Referring to Drawings 1, 2, 5, and 6 and paragraphs [0037]-[0041], [0057]-[0059], Morimoto discloses a magnetic field generator 23 for magnetron plasma, comprising a plurality of magnetic segments 24 provided on the outer side of a process chamber 2 for performing a predetermined process on a substrate placed in said chamber for generating a multi-pole magnetic field 25 along the circumference of said substrate.

Ito et al. or Morimoto fail to teach a magnetic field generator comprises an upper magnetic field generating mechanism and a lower magnetic field generating mechanism and in that said upper and lower magnetic field generating mechanisms are moved vertically in opposite directions toward a horizontal level at which the substrate is positioned to decrease the distance

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therebetween and are moved vertically in opposite directions away from the horizontal level to increase the distance therebetween.

Referring to paragraph [0002], Nishijima et al. teaches a magnetic field generator comprising an upper magnetic field generating mechanism 21 and a lower magnetic field generating mechanism 31 in order to confine the plasma. Thus, it would have been obvious to one of ordinary skill in the art at the time of the invention to modify the magnet field generator of Ito et al. or Morimoto to have an upper magnetic field generating mechanism 21 and a lower magnetic field generating mechanism 31 since this is an alternate arrangement for a magnet field generator that would enhance plasma confinement.

In addition, referring to Drawing 1 and paragraphs [0014]-[0019], Nishijima et al. teaches a plasma processing apparatus using a moving mechanism 22, 32 which vertically moves the upper and lower magnetic field generating mechanisms 21, 31 in opposite directions toward and away from a horizontal level at which the substrate is positioned in order to enhance plasma uniformity. Thus, it would have been obvious to one of ordinary skill in the art at the time of the invention to vertically move the upper and lower magnetic field generating mechanisms in opposite directions toward and away from a horizontal level at which the substrate is positioned using a moving mechanism as taught by Nishijima et al. in order to enhance plasma uniformity. In addition, when the magnets are vertically moved toward and away from each other, the intensity of the magnetic field will inherently change and thus the intensity can be controlled in this manner.

7. Claim 20 is rejected under 35 U.S.C. 103(a) as being unpatentable over Ito et al. (JP 2001-338912) or Morimoto (J.P. 2001-077095) in view of Arami et al. (US 6,014,943).

The teachings of Ito et al. or Morimoto have been discussed above.

Ito et al. or Morimoto fail to teach that each of the magnet segments is substantially in the shape of a cylinder.

It should be noted that Ito et al. (par.[0028]) discloses that the shape of the magnet segments can be altered. Referring to Figures 1-3 and column 6, lines 40-67, Arami et al. shows that it is conventionally known in the art for each of the magnet segments to be substantially in the shape of the cylinder. In addition, the shape of the claimed magnet segments is considered a matter of choice which a person of ordinary skill in the art would have found obvious absent persuasive evidence that the particular shape of the claimed magnet segments was significant. Thus, it would have been obvious to one of ordinary skill in the art at the time of the invention to modify the shape of the magnet segments of Ito et al. or Morimoto to be substantially cylindrical as taught by Arami et al. since the shape of the magnet segments is considered an obvious design choice to enhance the desired process.

Response to Arguments

8. Applicant's arguments filed April 09, 2010 have been fully considered but they are not persuasive.

Applicant has argued that the multipole magnetic field of Ito or Morimoto is different from a cylindrically shaped magnetic field of Nishijima et al. and thus one of ordinary skill would not have combined the references. It should be noted that Ito et al.'912 and Morimoto'095 were applied to teach the structure of a multi-pole magnetic field generator. Nishijima et al. was simply applied to teach the concept of vertically moving magnets toward and away from a horizontal level at which a substrate is positioned. Therefore, regardless of the

magnetic arrangement (i.e. cylindrical or multi-pole), when the magnets are vertically moved toward and away from each other, the intensity of the magnetic field will inherently change and thus the magnetic field intensity can be controlled in this manner. Furthermore, the motivation to combine Ito et al. or Morimoto with Nishijima et al. is to enhance plasma uniformity which will result in uniform substrate processing (i.e. deposition or etching). Therefore, the combination of Ito et al. or Morimoto in view of Nishijima et al. teaches a magnetic field generator wherein the intensity of the multi-pole magnetic field is controlled and thus satisfies the claimed requirements.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michelle Crowell whose telephone number is (571)272-1432. The examiner can normally be reached on M-Th (9:30 -6:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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/Michelle Crowell/ Examiner, Art Unit 1716

/Parviz Hassanzadeh/ Supervisory Patent Examiner, Art Unit 1716